Justin Bogan

List of Publications by Year in Descending Order

34 papers	375 citations	12 h-index	18 g-index
40 ext. papers	452 ext. citations	4.1 avg, IF	3.33 L-index

#	Paper	IF	Citations
34	The role of atomic oxygen in the decomposition of self-assembled monolayers during area-selective atomic layer deposition. *Applied Surface Science*, **2022**, 586, 152679	6.7	1
33	A new method for assessing the recyclability of powders within Powder Bed Fusion process. *Materials Characterization*, **2020**, 161, 110167	3.9	30
32	Area-Selective ALD of Ru on Nanometer-Scale Cu Lines through Dimerization of Amino-Functionalized Alkoxy Silane Passivation Films. *ACS Applied Materials & Interfaces*, **2020**, 12, 4678-4688	9.5	13
31	Analysis of Al and Cu salt infiltration into a poly 2-vinylpyridine (P2vP) polymer layer for area selective deposition applications. *Journal Physics D: Applied Physics*, **2020**, 53, 115105	3	4
30	Precise Definition of a "Monolayer Point" in Polymer Brush Films for Fabricating Highly Coherent TiO Thin Films by Vapor-Phase Infiltration. *Langmuir*, **2020**, 36, 12394-12402	4	5
29	Surface characterization of poly-2-vinylpyridine polymer for area selective deposition techniques. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2019**, 37, 050601	2.9	4
28	Hard x-ray photoelectron spectroscopy study of copper formation by metal salt inclusion in a polymer film. *Journal Physics D: Applied Physics*, **2019**, 52, 435301	3	7
27	Nitrogen reactive ion etch processes for the selective removal of poly-(4-vinylpyridine) in block copolymer films. *Nanotechnology*, **2018**, 29, 355302	3.4	3
26	Synchrotron radiation study of metallic titanium deposited on dielectric substrates. *Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics*, **2018**, 36, 040602	1.3	
25	Nucleation and adhesion of ultra-thin copper films on amino-terminated self-assembled monolayers. *Applied Surface Science*, **2018**, 462, 38-47	6.7	12
24	On the use of (3-trimethoxysilylpropyl)diethylenetriamine self-assembled monolayers as seed layers for the growth of Mn based copper diffusion barrier layers. *Applied Surface Science*, **2018**, 427, 260-266	6.7	18
23	Investigation of nitrogen incorporation into manganese based copper diffusion barrier layers for future interconnect applications. *Surfaces and Interfaces*, **2018**, 13, 133-138	4.1	4
22	Physical, chemical and electrical characterisation of the diffusion of copper in silicon dioxide and prevention via a CuAl alloy barrier layer system. *Materials Science in Semiconductor Processing*, **2017**, 63, 227-236	4.3	5
21	Exploring the Role of Adsorption and Surface State on the Hydrophobicity of Rare Earth Oxides. *ACS Applied Materials & Interfaces*, **2017**, 9, 13751-13760	9.5	46
20	Controlling wettability of PECVD-deposited dual organosilicon/carboxylic acid films to influence DNA hybridisation assay efficiency. *Journal of Materials Chemistry B*, **2017**, 5, 8378-8388	7.3	2
19	Chemical and electrical characterisation of the segregation of Al from a CuAl alloy (90%:10% wt) with thermal anneal. *Thin Solid Films*, **2016**, 599, 59-63	2.2	2
18	In Situ XPS Chemical Analysis of MnSiO3 Copper Diffusion Barrier Layer Formation and Simultaneous Fabrication of Metal Oxide Semiconductor Electrical Test MOS Structures. *ACS Applied Materials & Interfaces*, **2016**, 8, 2470-7	9.5	24

17	A photoemission study of the effectiveness of nickel, manganese, and cobalt based corrosion barriers for silicon photo-anodes during water oxidation. *Journal of Applied Physics*, **2016**, 119, 195301	2.5	1
16	In-situ surface and interface study of atomic oxygen modified carbon containing porous low- dielectric films for barrier layer applications. *Journal of Applied Physics*, **2016**, 120, 105305	2.5	7
15	The impact of porosity on the formation of manganese based copper diffusion barrier layers on low- dielectric materials. *Journal Physics D: Applied Physics*, **2015**, 48, 325102	3	5
14	Oxidation of ruthenium thin films using atomic oxygen. *Thin Solid Films*, **2015**, 597, 112-116	2.2	5
13	Photoemission study of the identification of Mn silicate barrier formation on carbon containing low- dielectrics. *Microelectronic Engineering*, **2014**, 130, 46-51	2.5	17
12	The addition of aluminium to ruthenium liner layers for use as copper diffusion barriers. *Applied Surface Science*, **2014**, 307, 677-681	6.7	4
11	Defect-mediated ferromagnetism in ZnO:Mn nanorods. *Applied Physics A: Materials Science and Processing*, **2014**, 115, 313-321	2.6	8
10	In Situ Investigations into the Mechanism of Oxygen Catalysis on Ruthenium/Manganese Surfaces and the Thermodynamic Stability of Ru/Mn-Based Copper Diffusion Barrier Layers. *Journal of Physical Chemistry C*, **2013**, 117, 16136-16143	3.8	7
9	Investigation of the release of Si from SiO2 during the formation of manganese/ruthenium barrier layers. *Applied Physics Letters*, **2013**, 102, 201603	3.4	3
8	Scanning transmission electron microscopy investigations of self-forming diffusion barrier formation in Cu(Mn) alloys on SiO2. *APL Materials*, **2013**, 1, 042105	5.7	15
7	Chemical and structural investigations of the incorporation of metal manganese into ruthenium thin films for use as copper diffusion barrier layers. *Applied Physics Letters*, **2012**, 101, 231603	3.4	9
6	Chemical and structural investigations of the interactions of Cu with MnSiO3 diffusion barrier layers. *Journal of Applied Physics*, **2012**, 112, 064507	2.5	13
5	STEM Analysis Of Cu(Mn) Self-Forming Diffusion Barriers on SiO2 For Applications In The Semiconductor Industry. *Microscopy and Microanalysis*, **2012**, 18, 1842-1843	0.5	
4	Chemical and structural investigation of the role of both Mn and Mn oxide in the formation of manganese silicate barrier layers on SiO2. *Journal of Applied Physics*, **2011**, 110, 054507	2.5	28
3	Synchrotron radiation photoemission study of in situ manganese silicate formation on SiO2 for barrier layer applications. *Applied Physics Letters*, **2011**, 98, 113508	3.4	26
2	Photoemission study of carbon depletion from ultralow- carbon doped oxide surfaces during the growth of Mn silicate barrier layers. *Journal of Applied Physics*, **2011**, 110, 124512	2.5	13
1	Interdiffusion and barrier layer formation in thermally evaporated Mn/Cu heterostructures on SiO2 substrates. *Applied Physics Letters*, **2011**, 98, 123112	3.4	34